



I.S.S.N. 09/941,537

+ IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Chen et al.

Group Art Unit: 1756

Serial No.: 09/941,537

Examiner: J. S. Ruggles

Filed: 08/29/2001

In Response to Office Action
Dated: 04/06/2004

Do NOT
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6/15/04
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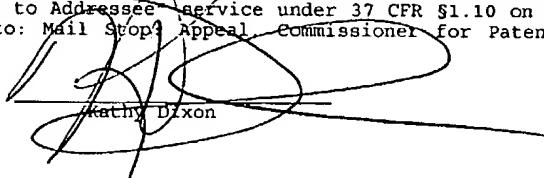
For: METHOD FOR REDUCING LIGHT REFLECTANCE IN A PHOTOLITHOGRAPHIC
DUAL DAMASCENE TRENCH PATTERNING PROCESS

Attorney Docket No.: 67,200-477

EXPRESS MAIL CERTIFICATE

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SUPPLEMENTAL AMENDMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, Va 22313-1450

Dear Sir:

In response to Advisory Actions mailed 04/06/2004

Applicants respectfully request entry of the following amendments to place the Application to remove issues from Appeal and comply with Examiners requirements and/or suggestions. Please consider the following remarks.